

10784510_CLS
Most Frequently Occurring Classifications of Patents Returned
From A Search of 10784510 on September 02, 2004

Original Classifications

11	250/492.2
6	250/492.21
3	250/309
2	250/252.1
2	250/281
2	250/283
2	250/492.3
2	359/484

Cross-Reference Classifications

12	250/397
9	250/398
5	250/492.3
3	250/281
3	250/282
3	250/288
3	250/492.2
3	315/111.81
2	118/715
2	250/251
2	250/298
2	250/423R
2	250/443.1
2	313/361.1
2	313/363.1
2	359/324

Combined Classifications

14	250/492.2
13	250/397
9	250/398
7	250/492.3
6	250/492.21
5	250/281
4	250/288
3	250/251
3	250/282
3	250/283
3	250/309
3	250/423R
3	315/111.81
2	118/715
2	250/252.1

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2 250/298
2 250/443.1
2 313/361.1
2 313/363.1
2 324/71.3
2 359/324
2 359/484
2 378/160
2 427/523

10784510_CLSTITLES

Titles of Most Frequently Occurring Classifications of Patents Returned

From A Search of 10784510 on September 02, 2004

- 14 250/492.2 (11 OR, 3 XR)
Class 250 : RADIANT ENERGY
250/492.1 IRRADIATION OF OBJECTS OR MATERIAL
250/492.2 .Irradiation of semiconductor devices
- 13 250/397 (1 OR, 12 XR)
Class 250 : RADIANT ENERGY
250/396R WITH CHARGED PARTICLE BEAM DEFLECTION OR
FOCUSSING
250/397 .With detector
- 9 250/398 (0 OR, 9 XR)
Class 250 : RADIANT ENERGY
250/396R WITH CHARGED PARTICLE BEAM DEFLECTION OR
FOCUSSING
250/398 .With target means
- 7 250/492.3 (2 OR, 5 XR)
Class 250 : RADIANT ENERGY
250/492.1 IRRADIATION OF OBJECTS OR MATERIAL
250/492.3 .Ion or electron beam irradiation
- 6 250/492.21 (6 OR, 0 XR)
Class 250 : RADIANT ENERGY
250/492.1 IRRADIATION OF OBJECTS OR MATERIAL
250/492.2 .Irradiation of semiconductor devices
250/492.21 ..Ion bombardment
- 5 250/281 (2 OR, 3 XR)
Class 250 : RADIANT ENERGY
250/281 IONIC SEPARATION OR ANALYSIS
- 4 250/288 (1 OR, 3 XR)
Class 250 : RADIANT ENERGY
250/281 IONIC SEPARATION OR ANALYSIS
250/288 .With sample supply means
- 3 250/251 (1 OR, 2 XR)
Class 250 : RADIANT ENERGY
250/251 ELECTRICALLY NEUTRAL MOLECULAR OR ATOMIC BEAM
DEVICES AND METHODS
- 3 250/282 (0 OR, 3 XR)

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	Class	250	:	RADIANT ENERGY
	250/281			IONIC SEPARATION OR ANALYSIS
	250/282			.Methods
3	250/283		(2 OR, 1 XR)	
	Class	250	:	RADIANT ENERGY
	250/281			IONIC SEPARATION OR ANALYSIS
	250/282			.Methods
	250/283			..With collection of ions
3	250/309		(3 OR, 0 XR)	
	Class	250	:	RADIANT ENERGY
	250/306			INSPECTION OF SOLIDS OR LIQUIDS BY CHARGED PARTICLES
	250/309			.Positive ion probe or microscope type
3	250/423R		(1 OR, 2 XR)	
	Class	250	:	RADIANT ENERGY
	250/423R			ION GENERATION
3	315/111.81		(0 OR, 3 XR)	
	Class	315	:	ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS
	315/111.01			DISCHARGE DEVICE LOAD WITH FLUENT MATERIAL SUPPLY TO THE DISCHARGE SPACE
	315/111.81			.Electron or ion source
2	118/715		(0 OR, 2 XR)	
	Class	118	:	COATING APPARATUS
	118/715			GAS OR VAPOR DEPOSITION
2	250/252.1		(2 OR, 0 XR)	
	Class	250	:	RADIANT ENERGY
	250/252.1			CALIBRATION OR STANDARDIZATION METHODS
2	250/298		(0 OR, 2 XR)	
	Class	250	:	RADIANT ENERGY
	250/281			IONIC SEPARATION OR ANALYSIS
	250/294			.Static field-type ion path-bending selecting means
	250/298			..Magnetic field path-bending means
2	250/443.1		(0 OR, 2 XR)	
	Class	250	:	RADIANT ENERGY
	250/306			INSPECTION OF SOLIDS OR LIQUIDS BY CHARGED PARTICLES
	250/440.11			.Analyte supports
	250/443.1			..With heat transfer or temperature-indication

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means

- 2 313/361.1 (0 OR, 2 XR)
Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES
313/359.1 WITH POSITIVE OR NEGATIVE ION ACCELERATION
313/361.1 .Means for deflecting or focusing
- 2 313/363.1 (0 OR, 2 XR)
Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES
313/359.1 WITH POSITIVE OR NEGATIVE ION ACCELERATION
313/363.1 .Extraction or target electrode
- 2 324/71.3 (1 OR, 1 XR)
Class 324 : ELECTRICITY: MEASURING AND TESTING
324/71.1 DETERMINING NONELECTRIC PROPERTIES BY MEASURING
G ELECTRIC PROPERTIES
324/71.3 .Beam of atomic particles
- 2 359/324 (0 OR, 2 XR)
Class 359 : OPTICS: SYSTEMS
359/237 OPTICAL MODULATOR
359/321 .Having particular chemical composition or
structure
359/324 ..Magneto-optic crystal material
- 2 359/484 (2 OR, 0 XR)
Class 359 : OPTICS: SYSTEMS
359/483 POLARIZATION WITHOUT MODULATION
359/484 .Time invariant electric, magnetic, or
electromagnetic field responsive (e.g., electro-optical,
magneto-optical)
- 2 378/160 (1 OR, 1 XR)
Class 378 : X-RAY OR GAMMA RAY SYSTEMS OR DEVICES
378/145 BEAM CONTROL
378/160 .Shutter or chopper
- 2 427/523 (1 OR, 1 XR)
Class 427 : COATING PROCESSES
427/457 DIRECT APPLICATION OF ELECTRICAL, MAGNETIC,
WAVE, OR PARTICULATE ENERGY
427/523 .Ion plating or implantation